Korean International Semiconductor Conference & Exhibition
on Manufacturing Technology 2025

# KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

## [WeD2] Material & Process

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| **Session Date** | November 12 (Wed.), 2025 |
| **Session Time** | 14:10-15:50 |
| **Session Room** | Room D (Sydney Room, 2F) |
| **Session Chair** | Prof. Su-Mi Hur (Chonnam Nat'l Univ., Korea) |

**[WeD2-1] [Invited]** **14:10-14:40**

**Advanced Patterning: Tackling the Big Problems in Printing Small Features**

Ben Eynon (Lam Research, USA)

**[WeD2-2] [Invited]** **14:40-15:10**

**Overview of Innovative Lithography Patterning Process Materials Contributing to Next Wave of Challenge on Semiconductor Architecture**

Ethan C B Lee, Seoung-Woo Jang, Sang-Hee Park, Byeri Yoon (Samsung SDI, Korea)

**[WeD2-3] [Invited]** **15:10-15:30**

**EUV vs. E-Beam Photoresists: Cross-Platform Analysis and Optimization Strategies**

Hyungkun Lee, Jaehyun Kim, Myounghyun Hur, Jeongwoo Kim, and Jeongsik Kim (Dongjin Semichem Co., Ltd., Korea)

**[WeD2-4] [Invited]** **15:30-15:50**

**EUV Mask Local CD Correction System Development via Laser Irradiation**

Hyun Yoon, Yujin Cho, Ki Hoon Choi, Hojong Hwang, Seung Eon Oh, Seryeyohan Cho, Jin Yeong Sung, Jangjin Lee, Taeshin Kim, Sang Hyeon Ryu, Youngho Park, Donggeun Lee, Joon Ho Won (SEMES, Korea), Yong Woo Kim, Jong Keun Oh, Jong Ju Park (Samsung Electronics Co., Ltd., Korea), and Byeonggeun Kim (SEMES, Korea)